• • •		Тур	e L	# Hits	Search Text	DBs	Time Stam	m e	r D	E
	1	BRS	L1	4032	iminodiacetic	USPAT; US-PGPUE EPO; JPO; DERWENT IBM_TDB	3; 2003/09/06 -, 13:29			0
	2	BRS	L2	38	1 and (CMP or "chemical mechanical polishing")	USPAT; US-PGPUE EPO; JPO; DERWENT IBM_TDB	3; 2003/09/06 14:40)
	3	BRS	L3	236	(thioester or thioether or carbothiolic or carbothionic or thiocarboxylic or tihisalicylic) and (CMP or "chemical mechanical polishing")	USPAT; US-PGPUB EPO; JPO; DERWENT IBM_TDB	; 2003/09/06 13:35		0)
	4	BRS	L4	12	3 and 438/\$.ccls.	USPAT; US-PGPUB EPO; JPO; DERWENT; IBM_TDB	2003/09/06 13:42		0	
5	5 . E	BRS	L5	41	((organic and inorganic) with (medium or media)) and (CMP or "chemical mechanical polishing")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/06 13:43		0	
6	E	BRS	L6	3	5 and 438/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/06 13:45		0	7
7	В	RS I	_7	3	((nonaqueous) with (medium or media)) and (CMP or "chemical mechanical polishing")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/06 15:10		0	
8	В	RS L	.8	66 (r	nonaqueous) and (CMP or "chemical nechanical polishing")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/06		0	

	Ту	oe .	L#	Hits	Search Text	DBs	Time Stamp	C ro o r m D m ef e in nt iti s o	Er ro rs
9	BR	S L	9	9	8 and 438/\$.ccls.	USPAT; US-PGPUB EPO; JPO; DERWENT IBM_TDB	2003/09/06		0
10	BR	S L	10	1270	("pad" with (nonabrasive or fixed)) and (CMP or "chemical mechanical polishing")	USPAT; US-PGPUB EPO; JPO; DERWENT; IBM_TDB	2003/09/06 15:27		0
11	BRS	S L	11	723	("pad" with (nonabrasive or fixed)) same (CMP or "chemical mechanical polishing")	USPAT; US-PGPUB EPO; JPO; DERWENT; IBM_TDB	2003/09/06 14:41		0
12	BRS	L1	12	174	11 and 438/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/06 15:17		0
13	BRS	L1	3	2	((nonaqueous) with (slurry)) and (CMP or "chemical mechanical polishing")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/06 15:13		0
14	BRS	L1	4	33	onemical mechanical polishing)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/06 15:17)
15	BRS	L1	5 4		(DMSO) and (CMP or "chemical mechanical polishing")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/06 15:17		
16	BRS	L16	6 2	23	15 and 438/\$.ccls.		2003/09/06	0	

	Турс	e L#	Hits	Search Text	DBs	Time Stamp	o m m e nt	ef in	Ei ro
17	BRS	L17	2514	(alcohol or ketone) and (CMP or "chemical mechanical polishing")	USPAT; US-PGPUB EPO; JPO; DERWENT; IBM_TDB	2003/09/06			0
18	BRS	L18	280	(alcohol or ketone) same (CMP or "chemical mechanical polishing")	USPAT; US-PGPUB EPO; JPO; DERWENT; IBM_TDB	2003/09/06 15:27			0
19	BRS	L19	100	(alcohol or ketone) with (CMP or "chemical mechanical polishing")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/06 15:55			0
20	BRS	L20	126	(carrier with (water or nonaqueous or organic or ketone or alcohol)) same(CMP or "chemical mechanical polishing")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/06 15:58		***************************************	0
21	BRS	L21	48	(carrier with (water or nonaqueous or organic or ketone or alcohol)) with (CMP or "chemical mechanical polishing")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/06 15:56			0
22	BRS	L22	18	21 and 438/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/06 15:57			0
23	BRS	L23	12	(carrier with (nonaqueous or organic or ketone or alcohol)) same(CMP or "chemical mechanical polishing")	FU JEU :	2003/09/06 15:58		C	2

٠.